

Magnetic and Electronic property of transition metal phosphides interface of Ni_xP/Fe₂P

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Transition metal Phosphide with Fe₂P-type structure is promising candidates for magnetic refrigerant materials.^[1] (Fe_{1-x}Ni_x)₂P exhibit ferromagnetic properties at room temperature for $x < 0.8$. The Curie temperature decreases with increasing x and it exhibit a Pauli paramagnet behavior for $x > 0.5$.^[2] The Curie temperature can be controlled by adjusting the ratio of Fe and Ni. Additionally, experimental and computational studies suggest that the magnetism of (Fe_{1-x}Ni_x)₂P involves mainly the Fe sites and little or no Ni sites.^[3] The change in the magnetic properties is consider to involve a change in electronic state due to the Fe and Ni substitution. However, there are few experimental investigations of magnetic properties and electronic states about the same system.

Recently, we have succeeded in fabricating Ni phosphide thin films on Fe₂P substrates. In generally, surfaces and interfaces often exhibit different magnetic properties from those in the bulk. It is interesting that the new magnetic properties will appear or not in this transition metal phosphide thin film and interface, however there is few reports about the magnetic properties of this kind of materials. In this study, we investigated the magnetic and electronic properties of the thin films and interfaces of Ni_xP/Fe₂P samples using X-ray magnetic circular dichroism (XMCD) and X-ray photoelectron spectroscopy (XPS) measurements.

Fe₂P(10-10) were cleaned by cycles of Ar⁺ ion sputtering (0.5 keV) and 750°C annealing. The cleaned surfaces showed c(2x2) Low energy electron diffraction (LEED) patterns. Ni atoms were deposited on the Fe₂P clean surface at 500°C, which induces phosphorization of the film owing to surface segregation of P atoms from the bulk.^[4] The thickness of thin film was controlled by amount of Ni. Prepared Ni_xP/Fe₂P samples exhibit c(2x2) LEED pattern. The XMCD measurement of Fe₂P(10-10) and Ni₂P(10-10) clean surfaces and Ni_xP/Fe₂P thin film samples were performed at BL14 of HiSOR at room temperature. The XPS measurement of those samples were performed at BL5U of UVSOR and BL3B of PF.

Firstly, we measured Fe L edge and Ni L edge XMCD spectra of the Ni_xP/Fe₂P sample. The thickness of nickel phosphide layer was estimated 5Å. The Fe L edge XMCD signal obtained from the Ni_xP/Fe₂P sample was significantly increased from that of clean Fe₂P substrate sample. Ni phosphides such as Ni₂P, Ni₃P, and NiP₃ are paramagnetic,^[5] and Ni₂P substrates did not show XMCD signals. On the other hand, Ni_xP/Fe₂P samples showed XMCD signals at the Ni L edge. The peak top energy of the Fe L₃ edge of the thin film sample is lower than that of the Fe₂P clean surface and the peak top energy of the Ni L₃ edge of the thin film sample is higher than that of Ni₂P clean surface.

Secondly, we measured Fe L edge XMCD spectra obtained from various thickness Ni_xP/Fe₂P samples as shown in Figure1. Thickness dependence of XMCD signal was confirmed. These results indicated that the interaction between the thin film and the substrate changed the Curie temperature of the substrate and magnetic property of Ni phosphide thin film.

Combining XMCD and XPS results, we will discuss about this relationship of magnetic and electronic properties $\text{Ni}_x\text{P}/\text{Fe}_2\text{P}$ samples.

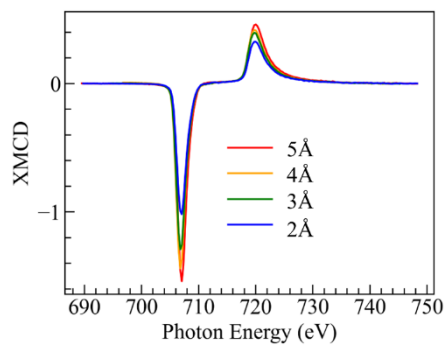


FIGURE 1. Fe L edge XMCD spectra obtained from various thickness $\text{Ni}_x\text{P}/\text{Fe}_2\text{P}$ samples.

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